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Fabrication and Radiation response of TaO_x based Resistive Random access memory (RRAM) devices

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Memory has been a basic building block for information technology. Among various memory technologies, Resistive Random Access Memory (RRAM) is an important element to replace the flash memory in future generation non-volatile memory applications. Recent studies have also proven its potential in harsh radiation environment of space. In this study, we present the effects of gamma irradiation on Tantalum oxide based RRAM devices. Indium tin oxide (ITO) coated glass was taken as bottom contact, on which Tantalum oxide (TaO_x) was grown using e-beam evaporation technique at different substrate temperatures (300 °C and 500 °C) during deposition. The top contact silver (Ag) was deposited using Thermal evaporation method. Surface morphological and electrical characterizations were performed on Ag/TaO_x/ITO RRAM devices. These devices were subjected to a wide range (100 Gy to 40 kGy) of doses of ⁶⁰Co Gamma irradiation. It was observed that the fabricated devices are sustainable even for heavy dose of 40 kGy. Defects created due to irradiation and their effects on switching properties of RRAM devices will be discussed in detail.